

Docket No.: 3273-0196PUS1  
(PATENT)

*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

In re Patent Application of:  
Shigeki KAMBARA, *et al.*

Conf.: 5132

Application No.: 10/519,998

Art Unit: 1752

Filed: January 5, 2005

Examiner: John CHU

For: PHOTORESIST RESIN AND PHOTORESIST  
RESIN COMPOSITION

**AMENDMENT UNDER 37 CFR 1.116**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**INTRODUCTORY COMMENTS**

*JK to  
attn  
Joe 12/2/06*

Responsive to the Office Action of August 9, 2006, the period for response being extended one month to December 9, 2006, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This response includes:

Amended Claim Set; and

Remarks.